

Controlled Growth of MoS₂ Flakes from in-Plane to Edge-Enriched 3D Network and Their Surface-Energy Studies

Abhay V. Agrawal,[†] Naveen Kumar,[†] Swaminathan Venkatesan,[‡] Alex Zakhidov,[‡] Christopher Manspecker,[§] Zhuan Zhu,^{||} FC Robles Hernandez,^{||} Jiming Bao,^{||} and Mukesh Kumar^{*,†}

[†]Department of Physics, Indian Institute of Technology Ropar, Rupnagar 140001, Punjab, India

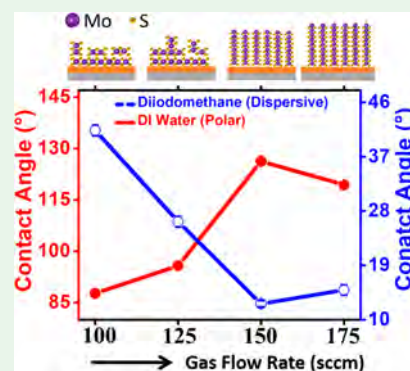
[‡]Department of Physics and [§]MSEC, Texas State University, San Marcos, Texas 78666, United States

^{||}Department of Electrical and Computer Engineering, University of Houston, Houston, Texas 77204, United States

Supporting Information

ABSTRACT: Controlled and tunable growth of chemically active edge sites over inert in-plane MoS₂ flakes is the key requirement to realize their vast number of applications in catalytic activities. Thermodynamically, growth of inert in-plane MoS₂ is preferred due to fewer active sites on its surface over the edge sites. Here, we demonstrate controlled and tunable growth from in-plane MoS₂ flakes to dense and electrically connected edge-enriched three-dimensional (3D) network of MoS₂ flakes by varying the gas flow rate using *tube-in-tube* chemical vapor deposition technique. Field emission scanning electron microscope results demonstrated that the density of edge-enriched MoS₂ flakes increase with increase in the gas flow rate. Raman and transmission electron microscopy analyses clearly revealed that the as-synthesized in-plane and edge-enriched MoS₂ flakes are few layers in nature. Atomic force microscopy measurement revealed that the growth of the edge-enriched MoS₂ takes place from the in-plane MoS₂ flakes. On the basis of the structural, morphological, and spectroscopic analysis, a detailed growth mechanism is proposed, where *in-plane* MoS₂ was found to work as a seed layer for the initial growth of edge-enriched vertically aligned MoS₂ flakes that finally leads to the growth of interconnected 3D network of edge-enriched MoS₂ flakes. The surface energy of MoS₂ flakes with different densities was evaluated by sessile contact angle measurement with deionized water (polar liquid) and diiodomethane (dispersive liquid). Both liquids show different nature with the increment in the density of the edge-enriched MoS₂ flakes. The total surface free energy was observed to increase with increase in the density of edge-enriched MoS₂ flakes. This work demonstrates the controlled growth of edge-enriched vertically aligned MoS₂ flakes and their surface-energy studies, which may be used to enhance their catalytic activities for next-generation green fuel production.

KEYWORDS: edge-enriched MoS₂ flakes, surface free energy, growth mechanism, CVD, contact angle



INTRODUCTION

Two-dimensional (2D) transition-metal dichalcogenides (TMDCs), especially MoS₂, have become research focus of scientific community owing to their unique electronic, physical, and chemical properties of atomically thin monolayer in contrast to their bulk counterpart and other 2D materials.^{1–4} MoS₂ monolayer has a direct band gap of 1.8 eV,⁴ which opens chances for its application in optoelectronics,² solar cells,⁵ water disinfection with visible light,⁶ and high ON–OFF ratio for next-generation nanoelectronic device applications.⁷ Moreover, MoS₂ has demonstrated potential application in catalytic activities like highly sensitive sensors, solar hydrogen production, electrochemical catalysis, and fuel cells.^{8–10}

To meet the next-generation clean-energy requirement, MoS₂ is being investigated in detail for noble-metal free electrocatalyst in hydrogen evolution reaction.^{8,9,11} To enhance the catalytic activity of MoS₂, the active edge sites are preferred over the inert in-plane MoS₂.⁹ Therefore, exposing more edges

of MoS₂ flakes by controlling its nanostructure allows the formation of more active electrocatalyst sites. However, thermodynamics favors the presence of in-plane growth, limiting the number of active sites at the MoS₂ surface. For hydrogen evolution reaction, the control density of the defects or edge-enriched MoS₂ flakes is critical. Therefore, controlled growth with variable density of edge-enriched MoS₂ flakes and understanding their growth mechanism would be one step closer to realize their great potential in catalytic applications.

To the best of our knowledge, there are limited reports in the literature to grow edge-enriched MoS₂ flakes, while there is no detailed report to grow controlled density of vertically aligned edge-enriched MoS₂ flakes, which may limit their great potential for different catalytic applications.^{12–15} Various

Received: March 23, 2018

Accepted: April 20, 2018

Published: April 20, 2018

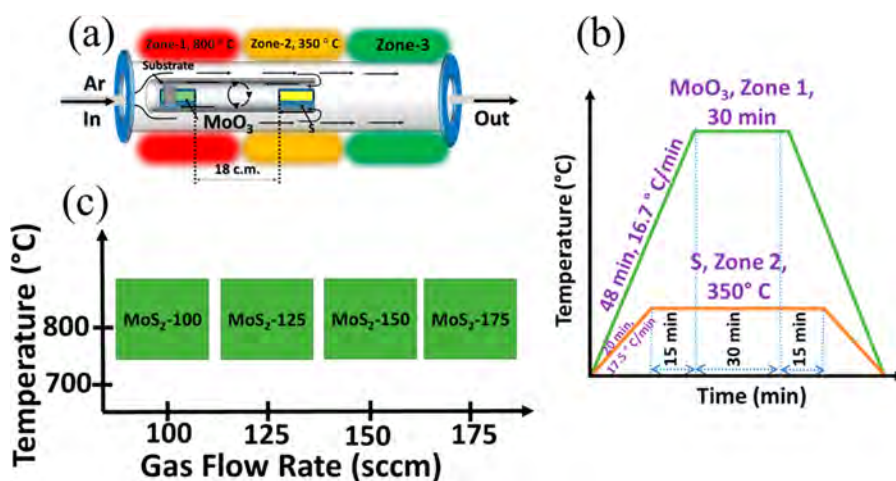


Figure 1. (a) Schematic of tube-in-tube APCVD technique used to grow edge-enriched vertically aligned MoS₂ flakes. SiO₂/Si substrate was placed on top of MoO₃ powder in zone 1, (b) temperature profile for MoO₃ and S powders in zone 1 and zone 2, respectively, and (c) the different growth conditions and nomenclatures of synthesized samples.

methods have been developed to synthesize different morphologies of MoS₂ materials.^{16,17}

It has been reported that MoS₂ flakes can be grown via hydrothermal synthesis or using molybdenum chloride as a precursor material.^{18–20} Furthermore, heterostructure growth of flowerlike structures has also been reported using graphene oxide as the template in a hydrothermal-assisted synthesis.^{21,22} On the one hand, these techniques, especially hydrothermal process, involve reaction times of over 12–24 h in addition to the use of dangerous precursors such as molybdenum chloride, which could potentially form harmful chloride vapors.²² On the other hand, atmospheric pressure chemical vapor deposition (APCVD) method has been reported for the growth of MoS₂ nanostructures including MoS₂ 2D flakes via sulphurization or decomposition of predeposited metal-based precursors or one-step reaction and deposition of gaseous metal and chalcogen feedstocks.^{23–30} The MoO₃ powder and S powder has been used as Mo and S source and heated at different temperatures in the simple APCVD chamber at atmospheric pressure.²⁰ The temperature gradient during growth and other parameters was found to impact the growth of MoS₂ nanostructures.³¹ These reports clearly showed the growth of either in-plane or edge-enriched MoS₂ flakes. However, there is no controlled and successive growth from in-plane to edge-enriched MoS₂ reported in literature.

In this work, we describe the large scale, uniform, and highly reproducible controlled growth from in-plane MoS₂ to edge-enriched MoS₂ in a modified tube-in-tube APCVD technique. The MoS₂ flakes were grown at different gas flow rates to control their density from standing alone MoS₂ flakes to well-connected three-dimensional (3D) MoS₂ flakes network. The detailed morphology, structural, and optical analyses of MoS₂ flakes revealed that the growth of vertical MoS₂ flakes starts from in-plane MoS₂, and with increase in gas flow rate, the density of edge-enriched MoS₂ flakes increases to a certain limit of gas flow followed by the growth of bigger flakes at higher gas flow rate. The growth of edge-enriched MoS₂ was also achieved on varieties of the substrates like SiO₂/Si, p-doped silicon, quartz, carbon fiber, and tungsten sheet using MoO₃ and S precursors. Finally, the surface energy of variable-density edge-enriched MoS₂ flakes was calculated by using polar and dispersive liquids in sessile drop contact angle. The results

reveal that the surface free energy of edge-enriched MoS₂ flakes is higher than in-plane MoS₂ layers. These results showed the method to grow control density of MoS₂ flakes and their surface-energy studies, which may be useful for next-generation hydrogen evolution reaction and their optimization.

EXPERIMENTAL SECTION

Synthesis of in-Plane MoS₂ Flakes to Edge-Enriched MoS₂ Flakes. The edge-enriched MoS₂ few layers with controlled density were synthesized on SiO₂/Si substrate using modified tube-in-tube growth chamber in the APCVD process. Before the growth, substrates were sonicated in acetone for 20 min and immediately cleaned with the nitrogen jet. High-purity MoO₃ (99.97%, Sigma-Aldrich) and sulfur powder (99.98%, Sigma-Aldrich) were loaded into two separate zirconia boats and placed in a small quartz tube closed at one end and open at other end having a diameter of 36 mm and length of 250 mm. This small quartz tube was inserted in a big quartz tube having a diameter of 55 mm and a length of 900 mm as shown in Figure 1a. The clean substrate was placed on the top of the boat containing MoO₃ powder at the closed end of the smaller tube, while the sulfur powder was placed at the opposite end of the small tube near the inlet of the small tube. This arrangement of small tube and precursor's boats was then placed into the three-zone APCVD furnace. The close end of the small tube, the substrate, and MoO₃ powder was in zone 1, and the open end and S powder was in zone 2. The distance between the MoO₃ and S powders was ~180 mm. The small tube was inserted into the big tube in such a way that closed end faced inflow. The schematic of the modified tube-in-tube APCVD process is shown in Figure 1a.

The furnace was initially purged with the high flow of argon (Ar; 300 sccm) for 20 min to fill the growth chamber with inert gas and prevent any other atmospheric gas reaction during the growth. After the furnace was purged, Ar flow rate was reduced and set according to different growth conditions. Zone 2 was heated first to create a sulfur-rich environment in the growth chamber. When the temperature of zone 2 reached 180 °C, zone 1 containing MoO₃ powder was also heated. The heating rates for zones 1 and 2 were 16.7 and 17.5 °C/min, respectively. The ramp rates for zones 1 and 2 are shown in Figure 1b. The growth temperature condition of the zones 1 and 2 was also set according to different growth condition. During growth, the temperature of the zone 3 reached 90 °C due to heat transfer from the zone 2 to zone 3. Growth time was 30 min in all the conditions followed by cooling to room temperature in argon ambient.

Nomenclature of As-Synthesized MoS₂ Sample. The nomenclature for the grown samples is shown in Figure 1c. The MoS₂ samples were synthesized at four different gas flow-rate conditions 100 sccm (MoS₂-100), 125 sccm (MoS₂-125), 150 sccm

(MoS₂-150), and 175 sccm (MoS₂-175). The gas flow rate for samples MoS₂-100 to MoS₂-175 was changed from 100 to 175 sccm with the interval of 25 sccm to study the effect of gas flow rate on MoS₂ growth at the fixed temperatures of 800 °C for zone 1 and 350 °C for zone 2, respectively.

Characterization of Synthesized MoS₂ Sample. The grown MoS₂ samples were characterized by using field emission scanning electron microscope (FE-SEM) and Raman and photoluminescence (PL) spectroscopies. FE-SEM imaging was performed using FEI Helios NanoLab 400 with a probe current of 0.34 nA and 10 kV of an accelerating voltage. The FEI Helios NanoLab 400 is equipped with energy-dispersive X-ray spectroscopy (EDS). The PL and Raman spectra were measured using a home-built micro-PL/Raman system consisting of HORIBA iHR 320 Spectrometer equipped with Synapse CCD, 532 nm continuous-wave laser, and a 100× objective lens. The 532 nm laser was used as the excitation source, and its power was fixed at 500 μW to avoid any heating to the samples. The laser spot size was ~0.5 μm. The same sample area was used for both PL and Raman measurements. The measurements were performed under ambient condition (25 °C and 45% relative humidity (RH)). The silicon 519 cm⁻¹ Raman peak was used as the reference for the system calibration. The laser wavelength setting in the spectrometer software was fine-tuned, until the laser line and silicon Raman peak line are at 0 and 519 cm⁻¹, respectively. Before the measurements, system was calibrated against the standard silicon peak at 519 cm⁻¹ for all four MoS₂ samples.

X-ray photoelectron spectroscopy (XPS) measurements were conducted using a high-resolution (HR) Gammadata Scienta SES-2002 operating in an ultrahigh vacuum and using SES software 1.2.5. A monochromatic Al X-ray source (1486.6 eV, anode operating at 12 kV and 150 W) was used as the incident radiation source. Survey scans were done on each sample at a pass energy of 100 eV prior to the elemental scans. Pass energy for the elemental scans was varied from 20 to 50 eV depending on the sample.

X-ray diffraction (XRD) measurements were conducted using the Rigaku Smart Lab X-ray Diffractometer using the Smart lab Guidance software. A Cu X-ray source operating at 40 kV and 44 mA was used as the incident radiation source and operated in the Bragg–Brentano high-resolution configuration. The HR-TEM images were made in a JEOL 2000 FX TEM operated using an accelerating voltage of 200 kV with a 0.28 nm resolution. The samples were prepared from scratching the MoS₂ film deposited over the Si substrate over a holey carbon Cu grid 300 mesh.

Contact Angle Measurements. The surface wetting properties of edge-enriched MoS₂ flakes with variable density were measured with fully automatic and computer-controlled contact angle measurement setup (Apex Instruments (ACAM-S1)). The contact angle measurement system was equipped with automatic droplet dispenser for precise and accurate measurement. The droplet size was kept at 3 μL to avoid the effect of gravity on the measurement. Further, surface energies for different MoS₂ samples were calculated by using Fowkes method. The contact angle with both the liquids was performed at multiple places on 1 × 2 cm² substrate size, and an average value of contact angle is reported.

RESULTS AND DISCUSSION

FE-SEM results of MoS₂ flakes grown at 100, 125, 150, and 175 sccm gas flow rate at 800 °C in modified APCVD system are shown in Figure 2. It is clear from the FE-SEM image in Figure 2a that isolated edge-enriched MoS₂ flakes are observed at 100 sccm gas flow rate. A few of the flakes are combined and form starlike structures. In MoS₂-125 sample, Figure 2b, the density of edge-enriched MoS₂ flakes increases in patches, while in MoS₂-150 sample, Figure 2c, the density increases more uniformly. As the gas flow rate increases to 175 sccm, a well-connected 3D network of edge-enriched MoS₂ flakes were observed, Figure 2d. It has been observed from the SEM images in MoS₂-100 and MoS₂-175 sample, that the flake sizes are

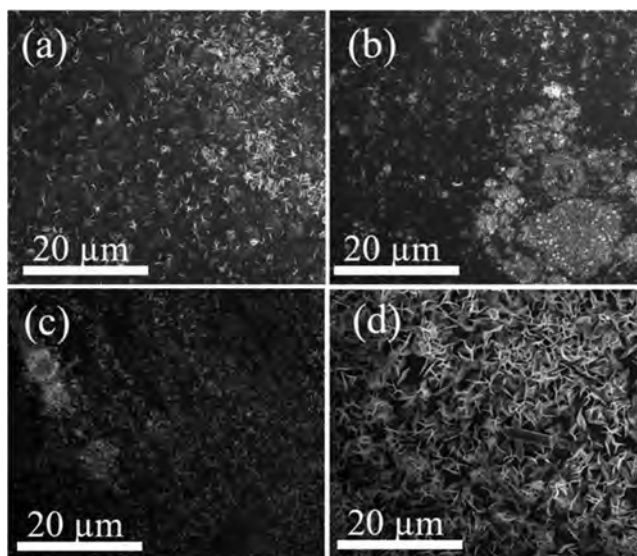


Figure 2. FE-SEM images of edge-enriched MoS₂ flakes grown at different gas flow rates of (a) 100, (b) 125, (c) 150, and (d) 175 sccm. The growth temperature for all these samples was fixed at 800 °C.

larger in nature than MoS₂ flakes for MoS₂-125 and MoS₂-150 samples. Because of larger size of the MoS₂ flakes in MoS₂-175 sample, the density of the edge-enriched MoS₂ flakes is lower in comparison to MoS₂-150. To analyze the edge-enriched MoS₂ flakes more closely, high-resolution imaging was performed, and FE-SEM images are shown in Figure 3a–d.

Figure 3a shows the FE-SEM image at MoS₂-100 sample and reveals less dense nature of edge-enriched MoS₂ flakes. For MoS₂-125 sample, flakes become more connected and dense, while with further increase in gas flow rate the density of edge-enriched MoS₂ flakes increases more uniformly. However, it was observed that the MoS₂ flakes grow bigger in size for the

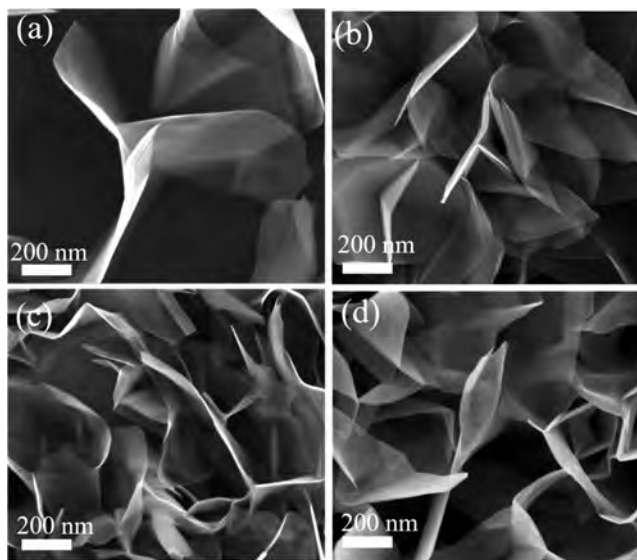


Figure 3. HR FE-SEM images of edge-enriched MoS₂ sample grown at (a) 100, (b) 125, (c) 150, and (d) 175 sccm argon flow and at 800 °C temperature. FE-SEM images clearly revealed the density of MoS₂ flakes is increased continuously from MoS₂-100 and MoS₂-125 to MoS₂-150, while the size of flakes is increased for MoS₂-175 with comparatively lower density.

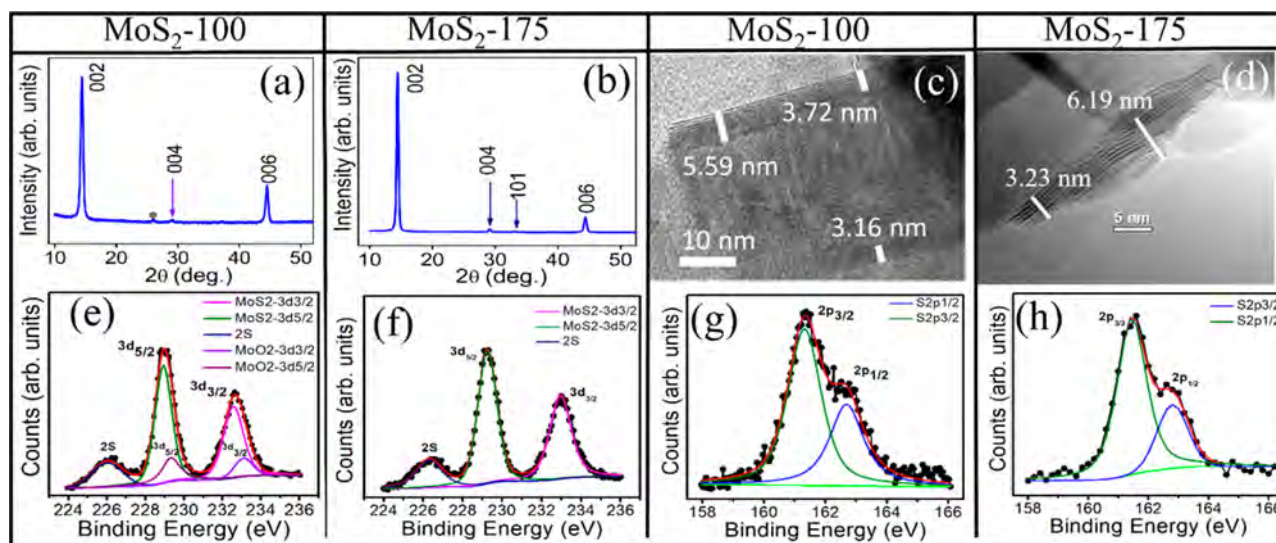


Figure 4. (a, b). XRD spectra acquired from the sample MoS₂-100 and MoS₂-175. (c, d) Cross-sectional TEM images of edge-enriched flakes obtained from the MoS₂-100 and MoS₂-175 sample. XPS scan of the samples. (e–h) HR elemental scan for Mo and S for MoS₂-100 and MoS₂-175.

MoS₂-175 sample, and the number of edge-enriched flakes per unit area decreased. The optical images and the color contrast of the as-synthesized four samples is shown in the Supporting Information (Figure S1). The SEM images shown in Figure S1 clearly revealed the quality of the uniform growth of as-prepared MoS₂ flakes on four samples over the large area. The uniform growth area of the as-synthesized MoS₂ flakes varied from 1 × 2 cm² to 1 in² on SiO₂/Si substrate.

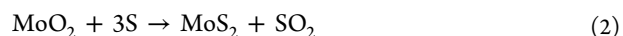
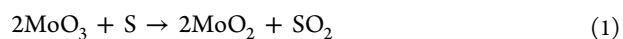
The tube-in-tube arrangement plays an important role to achieve uniform and controlled growth of MoS₂ flakes on large area. In one tube circular CVD setup the gas fluid has the maximum velocity at the center of the tube and zero velocity at the surface of the tube wall. So, the diffusion of the precursors is very high, which led to the fast and random nucleation of the MoS₂ on the substrate.^{24,29,30} However, in tube-in-tube arrangement, the gas flow rate is very smaller at the closed end of the small tube than the gas velocity at the inlet of small tube.³² Thus, MoS₂ vapor formed by the vaporization of the S and MoO₃ powder deposited slowly on the substrate. Therefore, the tube-in-tube setup plays an important role to control the nucleation density and the uniformity even over the large region.

The growth of MoS₂ flakes under optimized condition for edge-enriched flakes (175 sccm and 800 °C) was repeated on different substrates like carbon fiber, highly doped p-type Si, W sheet, and quartz substrates. We observed uniform and large area (1 × 2 cm²) growth of edge-enriched MoS₂ flakes. The optical images and FE-SEM images of MoS₂ flakes grown on the varieties of substrates are shown in Figure S2 of Supporting Information. The surface morphology of MoS₂ flakes clearly reveals that the present study is highly reproducible to grow highly uniform MoS₂ flakes even on different substrates.

To understand and confirm the structural, morphological, and chemical compositions of the as-grown MoS₂ samples, we performed and analyzed XRD on all four samples. TEM and XPS were performed only for the two extreme samples MoS₂-100 and MoS₂-175. The MoS₂-100 sample contains the mostly in-plane MoS₂ flakes, and as we increased the gas flow rate, the density of edge-enriched MoS₂ flakes increases, and MoS₂-175 sample contains highly uniform and dense edge-enriched MoS₂

flakes. Thus, we chose these two extreme samples. Figure 4 shows the XRD, cross-sectional TEM, and XPS results.

The XRD spectra for the sample MoS₂-100 and MoS₂-175 are shown in Figure 4a,b. In MoS₂-100, three peaks are observed, namely, two high intense peaks and one weak peak at 14.40°, 44.5°, and 29.08°. These peaks are for the plane of MoS₂ corresponding to the (002), (006), and (004) with respect to the JCPDS Card No. 37-1492. The (002) peak is representative for the out-of-plane MoS₂.³³ One very small peak, which may be due to reduced MoO₃, is also observed at 26.00°, marked with star. During the synthesis, MoO₃ powder first converts to the reduced MoO₃, followed by the sulfurization process, which results in the MoS₂ formation. The possible chemical reaction is given in eqs 1 and (2).^{34–36}



For MoS₂-175, we are getting the four peaks 14.40°, 29.03°, 33.07°, and 44.29°, which correspond to (002), (004), (101), and (006) planes. The peak corresponding to MoO₂ is completely disappeared, which clearly shows the increase in the uniformity of the MoS₂. Furthermore, the peaks in the case of the MoS₂-175 become more intense and sharp. The XRD corresponding to the other two samples MoS₂-125 and MoS₂-150 is shown in Figure S4 in the Supporting Information. The intensity of (002) peak is increased with increase in the density of the edge-enriched MoS₂ flakes.^{14,37}

The typical cross-sectional TEM performed on MoS₂-100 and MoS₂-175 samples to determine the number of the layers in the flakes are shown in Figure 4c,d.²⁶ Figure 4c shows that the edge-enriched MoS₂ flakes of different thickness ranging from 1.98 to 4.08 nm implies that MoS₂-100 sample has 3–6 layers of edge-enriched MoS₂ flakes.³⁸ In the case of the MoS₂-175 sample, the cross-sectional TEM data of edge-enriched MoS₂ flakes are shown in Figure 4d. The results reveal that edge-enriched MoS₂ flakes MoS₂ flakes are of 4–8 layers, in nature. Therefore, as the gas flow rate increases the number of layer in edge-enriched flakes may be increasing.

The great majority of edge-enriched MoS₂ flakes MoS₂ nanosheets have thicknesses varying from 3.15 to 5.6 nm

having an average d -spacing of $d = 0.62 \pm 0.1$ nm that is characteristic of the (001) plane of MoS₂ having a $P3m1$ symmetry.³⁹ The above results were made in more than 50 nanosheets, and here are presented only the averages and representative images to demonstrate the sample consistency. Furthermore, some of the investigated MoS₂ nanosheets are double or triple layers with thicknesses of 0.62 and 1.83 nm, respectively. Some more TEM images are shown in the Supporting Information as the Figure S5 for these two samples.

The chemical composition and stoichiometry analysis were performed for the samples MoS₂-100 and MoS₂-175 by using XPS, and results are shown in Figure 4e–h. All of the XPS data are calibrated with the adventitious carbon 1s peak at 284.8 eV. Figure 4e shows the XPS data corresponding to the MoS₂-100. The lower binding energy peak of 3d5/2 (229.1 eV) and 3d3/2 states (232.8 eV) correspond to the MoS₂, while high binding energy peak of 3d5/2 (229.5 eV) and 3d3/2 states (233.3 eV) correspond to the MoO₂. These respective 3d5/2 and 3d3/2 peaks confirm the presence of MoS₂ and MoO₂ in the MoS₂-100 sample, while in sample MoS₂-175 in Figure 4f, there is no presence of the MoO₂ seen, as the Mo 3d peaks are very sharp in nature, which reveals the single oxidation of Mo corresponding to MoS₂.

The high-resolution XPS of S 2p spectrum deconvoluted into two doublets S 2p3/2 and 2p1/2 peaks, which correspond to S²⁻ as shown in Figure 4g,h.²⁸ The binding energy for the S 2p3/2 and S 2p1/2 peaks were ascribed at 161.3 and 162.6 eV for the MoS₂-100 sample while at 161.4 and 162.8 eV for the MoS₂-175. The XPS analysis revealed that the chemical composition of two extreme samples, MoS₂-100 and MoS₂-175, is well matched with MoS₂.^{26,40}

The MoS₂ edge-enriched flakes were characterized by Raman and PL spectroscopies, and the data are shown in Figure 5a,b.

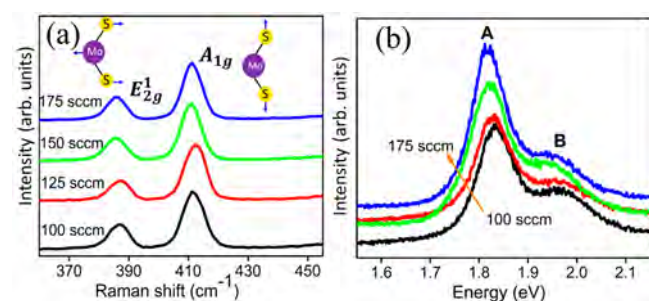


Figure 5. Representative (a) Raman and (b) PL spectra at the different positions from MoS₂ flakes samples grown at different gas flow rate. Raman spectra consist of two strong peaks that correspond to in-plane, E_{2g}¹, and out-of-plane, A_{1g}, vibrations of S–Mo–S atoms. The two PL peaks at 1.8 and 1.9 eV were observed.

Two Raman peaks near 400 cm⁻¹ correspond to *in-plane* (E_{2g}¹) and *out-of-plane* (A_{1g}) vibrations of S–Mo–S atoms in MoS₂ molecules.³⁴ The peak position, intensity, difference of the Raman shift for the ($\Delta = A_{1g} - E_{2g}^1$) and intensity ratio (E_{2g}¹/A_{1g}) for two peaks in all four samples are summarized in Table 1. To check the uniformity and quality of MoS₂ flakes, Raman data were taken at different areas. The *in-plane* vibration mode was observed to vary from 384 to 388 cm⁻¹, while *out-of-plane* vibration mode was varied from 407 to 411 cm⁻¹. It is found that MoS₂ flakes grown at different gas flow rate have the frequency difference (Δ) between the two Raman modes in the range of 18–26 cm⁻¹, which indicates that the as-grown MoS₂ flakes are monolayer to few layers in nature.^{41,42}

In the case of the E_{2g}¹ peak, the Mo atom vibrates in in-plane and opposite to two S atoms as shown in the Figure 5a, while for A_{1g} mode Mo atom is in rest, and two S atoms vibrate in opposite direction in out-of-plane.³⁴ Thus, E_{2g}¹ vibration preferentially excited for the terrace-terminated MoS₂ flakes, and the A_{1g} is for the edge-enriched MoS₂. So, the E_{2g}¹ mode is preferred by the terrace sites, and A_{1g} mode is preferred by the edges of the MoS₂. Therefore, the intensity arises due to E_{2g}¹ mode representing the existence of the in-plane MoS₂ flakes, while the intensity due to the A_{1g} mode represents the edge-enriched MoS₂ flakes.²⁷ As the density of the edge-enriched MoS₂ flakes increases, the intensity due to out-of-plane vibration mode A_{1g} increases. Because of increase density of the edge-enriched MoS₂, density of the in-plane MoS₂ flakes decreases, and correspondingly the intensity of the E_{2g}¹ mode decreases. Hence, with increase of the edge-enriched MoS₂ flakes, the ratio of E_{2g}¹ to A_{1g} decreases.²⁶ MoS₂ flakes synthesized at 100 sccm have the E_{2g}¹/A_{1g} ratio of ~0.58–0.47 at different areas. The high value of E_{2g}¹/A_{1g} at different areas implies the synthesized flakes in the sample are mostly *in-plane* MoS₂. At 125 sccm gas flow rate, this ratio reduces and is found to vary from 0.55 to 0.43 for different areas and confirms the growth of vertical aligned MoS₂ flakes. However, for the MoS₂ flakes synthesized at 150 and 175 sccm, E_{2g}¹/A_{1g} ratio is ~0.42–0.39 for the different areas.

This continuous decrease in the ratio shows the density of edge-enriched flakes increases with gas flow rates. The variation in frequency difference (Δ) may be due to the mixed signal from the single layer, bilayer, and few layers MoS₂ flakes. The single, dual, and a few layer MoS₂ flakes were observed under HR-TEM. The photoluminescence data of different MoS₂ flakes samples are shown in Figure 5b. In all the MoS₂ flakes grown at different conditions, we detected two peaks of different intensities. One peak (named as A) is located in the energy range of 1.82–1.84 eV, while another peak of low intensity is located in the energy range of 1.94–1.98 eV (named as B). The peak at A is due to direct excitonic transition at the

Table 1. Raman and PL Data for Different MoS₂ Samples^a

sample	Raman spectroscopy				PL spectroscopy			
	position, cm ⁻¹		intensity, au		$\Delta(A_{1g} - E_{2g}^1)$	$I(E_{2g}^1/A_{1g})$	peak position, eV	
	E _{2g} ¹	A _{1g}	E _{2g} ¹	A _{1g}			A	B
MoS ₂ -100	386.6	411.2	46.9	99.3	24.6	0.47	1.83	1.98
MoS ₂ -125	385.3	411.1	42.9	99.9	25.7	0.43	1.82	1.95
MoS ₂ -150	387.6	412.3	40.3	100.1	24.7	0.40	1.82	1.94
MoS ₂ -175	386.1	411.1	39.7	99.7	24.9	0.39	1.82	1.94

^aRaman data show the peak position and intensity corresponding to E_{2g}¹ and A_{1g} modes along with the differences in two peaks ($\Delta A_{1g} - E_{2g}^1$) and their intensity ratio $I(E_{2g}^1/A_{1g})$. The peak positions for both PL signals are shown as A and B, respectively.

K-point of the Brillouin zone from K_4 to K_5 , and peak B is due to exciton transition from K_1 to K_5 .^{43,44} The peak position for peak A and peak B and other data are listed in Table 1.

The intensity variation within the different samples may depend strongly on the various parameters like thickness, defects, strain, and heights of MoS₂ flakes.⁴⁵ To understand the growth mechanism, we closely investigated MoS₂-100 sample by using FE-SEM and Raman and PL spectroscopies, and the results are shown in Figure 6a–d. Figure 6a shows the optical

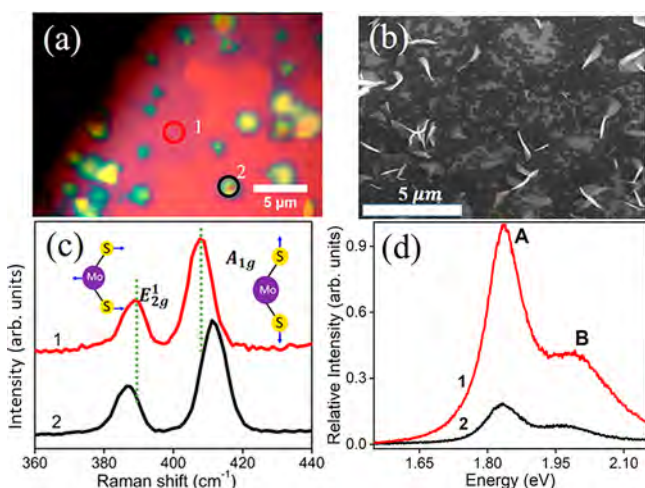


Figure 6. (a) The optical image of MoS₂-100 sample, area 1, corresponds to monolayer of MoS₂ flakes, and the area 2 corresponds to multilayer MoS₂ flakes of the same sample at different location. (b) FE-SEM image of MoS₂-100 sample. (c) Raman and (d) PL spectra recorded at the marked area of the sample.

image, and Figure 6b is FE-SEM image of MoS₂-100 sample. Figure 6c shows Raman measurements at two different areas marked as 1 and 2. At areas 1 and 2, two Raman peaks corresponding to E_{2g}^1 and A_{1g} modes of vibration at the 388.5, 407.1 and 386.5, 411.1 cm^{-1} , respectively, were observed. The observed peak position is similar to previous reports.³⁴ The E_{2g}^1 mode is red-shifted by 2.0 cm^{-1} , while the A_{1g} mode is blue-shifted by 4.1 cm^{-1} on area 2 with respect to area 1.

This shift is spotted when the number of layers in MoS₂ increases from a monolayer to few layers.⁴¹ This behavior of a blue shift in A_{1g} mode is quite strange according to the classical model of coupled harmonic oscillator.⁴⁶ In MoS₂, van der Waals interaction is responsible for the bonding of the two consecutive layers, so the restoring force on each atom is increased with the addition of each layer. Therefore, both modes should be stiffened with increment in the number of MoS₂ layers. However, experimentally, there is a discrepancy in this prediction, and this is termed as Davydov splitting.^{47,48} It reveals that frequency shift is not only affected by the van der Waals interlayer coupling but surface reconstruction and long-range Coulomb interaction also play an important role.^{39,49}

The frequency difference between the E_{2g}^1 and A_{1g} modes for area 1 and area 2 was found to be ~ 18.6 and 24.6 cm^{-1} , which were reported for monolayer and few layers of MoS₂ flakes, respectively.⁴¹ This finding is in good agreement with the HRTEM results, where we can observe those single, double, and few layers frameworks. Figure 6d shows the photoluminescence spectra obtained from the same areas as for Raman measurement. The relative PL intensity for the area 1 and area 2 is plotted. The two peaks A and B are at the energy

673.8 nm/1.84 eV and 627.1 nm/1.98 eV for the area 1 and 677.5 nm/1.83 eV and 632.5 nm/1.96 eV for the area 2. The Relative PL intensity for area 2 is only 18% of the PL intensity for the area 1. Thus, the higher PL intensity is further confirming the monolayer MoS₂ flakes in the area 1 and the few layer flakes in area 2. Therefore, MoS₂-100 sample is the mixture of *in-plane* monolayer and *out-of-plane* isolated few edge-enriched MoS₂ flakes.

To further explore and understand the growth mechanism of the edge-enriched MoS₂ flakes, we focus on the modified *tube-in-tube* process. It was observed that the modified *tube-in-tube* arrangement plays a vital role in the growth of edge-enriched MoS₂ flakes. The increased gas flow rates only provide an easy control for the density of flakes and with higher gas flow rates eventually formed 3D interconnected network of MoS₂ flakes seen in MoS₂-175 sample. As we can see in the Experimental Section, we used a modified *tube-in-tube* chemical vapor deposition system. The closed end of small tube is placed facing to the inflow of the gas in a big tube. The positioning of the small tube inside the larger tube results in the decrease of the gas flow rate inside the smaller tube by ~ 5 – 6 orders of magnitude than the gas flow rate/velocity at the open end of the small tube.³² This reduces the deposition rate and allows nucleation sites to grow very slowly. Observed growth took 30 min as compared to the other reports in literature, where the growth time is much shorter, occurring in 5–10 min.

To understand the growth in detail, we proposed the following three-step process involved in the formation of 3D interconnected MoS₂ flakes from individual in-plane MoS₂ flakes: (i) precursor stage, (ii) nucleation stage, and finally (iii) growth stage. Figure 7 shows schematic and final FE-SEM image, morphology stage, of the as-grown MoS₂ sample. In the precursor stage, MoO₃ powder and S powder vaporized at the growth temperature in their respective zones and formed MoS₂ as mentioned in eqs 1 and 2. The condensed MoS₂ on the substrate was initially small in size, mostly monolayer and few

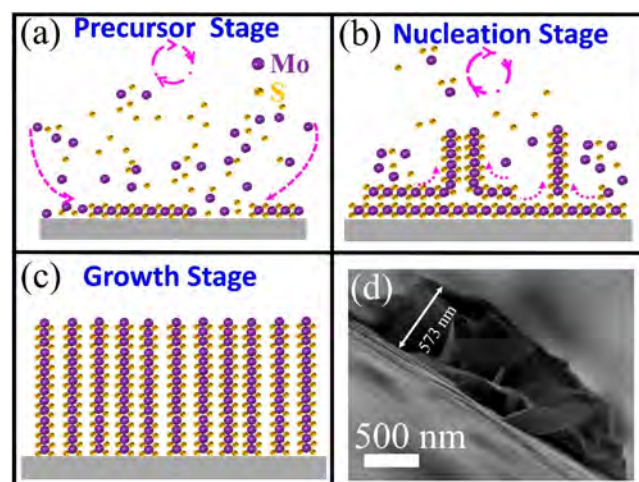


Figure 7. Proposed growth mechanism for edge-enriched MoS₂ flakes. (a) The precursor stage during the initial growth of in-plane MoS₂. In this stage of growth, in-plane MoS₂ is more, which results in monolayer to multilayer flakes formation on the substrate. (b) Nucleation stage for the growth of edge-enriched flakes. The incoming S and Mo atoms adsorbed on the substrate and on the MoS₂ flakes and start the growth of edge-enriched flakes. (c) Schematic shows the growth stage for final as-grown interconnected MoS₂ flakes. (d) Cross-sectional FE-SEM image of the edge-enriched MoS₂ flakes.

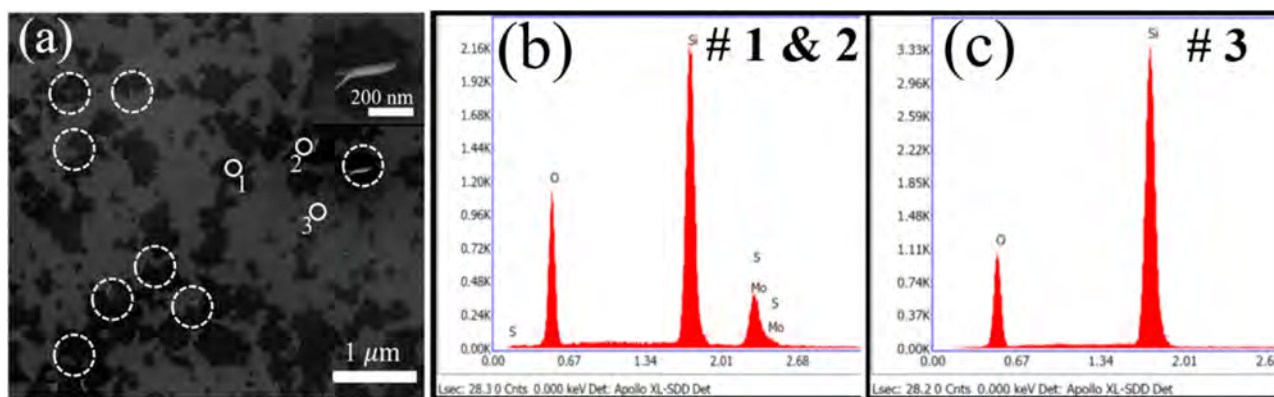


Figure 8. (a) FE-SEM image of the MoS₂-175 @ 700. (inset) The high-magnification FE-SEM image of isolated MoS₂ flakes. Spot EDS was recorded at the marked locations #1–3. (b, c) Spot EDS at locations #1 and #2 were observed similar, while EDS at base substrate site, spot #3.

layers in size, as shown in the schematic of Figure 7a. It provides the seeding platform for the further growth of edge-enriched MoS₂ flakes.

In nucleation stage, with increased growth time, the size of the condensed MoS₂ on the substrate increases, and thickness is also increased.⁴⁵ After a certain critical thickness, surface free energy increases, which also increases the strain. Thus, curling force at the boundaries effects the extension of the film and changes the alignment of the film from the 2D in-plane growth to 3D out-of-the-plane growth, as shown in the schematic of Figure 7b. The transition from 2D in-plane to vertically aligned MoS₂ flakes follows a standard Stranski–Krastanov (SK) growth model, where after forming one or more monolayer subsequent in-plane growth of MoS₂ becomes unfavorable, and island or vertically aligned MoS₂ forms. Wang et al. and others reported the synthesis of edge-enriched MoS₂ flakes using solvothermal and hydrothermal method and edge-enriched MoS₂ flakes. The MoS₂ flakes were observed to grow on the defective sites.^{27,37,50,51} However, in our case, first in-plane MoS₂ flakes grow on the substrate followed by edge-enriched MoS₂ flakes due to the coalescence and changing the orientation from in-plane MoS₂ flakes to vertical MoS₂ flakes as time continues during single step. To further confirm this hypothesis, we performed atomic force microscopic measurement on in-place MoS₂ specifically where the growth of edge-enriched MoS₂ flakes just started. The AFM results, added as Figure S7 of Supporting Information, clearly reveal the layer-by-layer growth of in-plane MoS₂ and formation of edge-enriched MoS₂ on top of in-plane MoS₂ flakes.

The transition from 2D to 3D growth is not completely understood, but any factor that disturbs the monotonic decrease in the binding energy characteristic of layer growth like stress or other factors may be responsible for this.⁵² Thus, the growth of edge-enriched MoS₂ flakes is the combination of the *in-plane* and *out-of-plane* growth. The *in-plane* MoS₂ flakes then provide the seeding platform for the further growth of edge-enriched MoS₂ flakes. This can be seen from Figure 7b, where edge-enriched MoS₂ flakes are grown up only where the coalescence takes place.^{25,52}

To test the proposed growth mechanism and observe the onset of growth for MoS₂ edge-enriched flakes on *in-plane* MoS₂ flakes, we performed the growth of MoS₂ at a lower temperature of 700 °C and at 100 sccm keeping other conditions identical. It is observed that no deposition occurred at this condition. Keeping the temperature fixed, we increased the gas flow rate from 100 to 175 sccm. At 700 °C and 175

sccm gas flow rate, the initial growth (black patches) were found. The FE-SEM and EDS result are shown in Figure 8a–c.

Figure 8a shows the FE-SEM image of initial growth with black patches and few marked nucleation sites. It is clear from the Figure 8a that onset growth of vertically aligned MoS₂ only takes place on top of *in-plane* MoS₂ flakes. The black multilayer MoS₂ patches may be formed due to coalescing process. The coalescence process is evident from patches like structures of *in-plane* MoS₂, which may be formed due to the several mass transport mechanisms like Ostwald ripening, sintering, or cluster migration.⁵²

The EDS performed at different locations is given in Figure 8b,c, which further confirms that black patches are MoS₂ flakes on the base SiO₂/Si substrate. The O peak is coming from the base SiO₂ on Si substrate. The FE-SEM results clearly indicate that *in-plane* MoS₂ grows on the substrate and acts as the seed layer for the further growth of vertically aligned MoS₂ flakes.

With higher gas flow rate, condensation of the MoS₂ increases, which leads to more coalescence of the *in-plane* MoS₂, resulting in more favorable seed sites for the growth of edge-enriched MoS₂ flakes. For the MoS₂-100 sample, gas flow rate is small, so the MoS₂ flakes have enough time to condense on the substrate, and they slowly formed the *in-plane* MoS₂ flakes. At the same time in some regions, due to coalescence, the edge-enriched MoS₂ flakes start forming as shown in Figure 2a. So, the MoS₂ vapor also started to condense at these edge-enriched MoS₂ flakes. Thus, the height of edge-enriched MoS₂ flakes increased with time.

As the gas flow rate increased to 125 and 150 sccm, *in-plane* MoS₂ condensed on the substrate in much less time than the samples grown up to 100 sccm and provided more seeding platform for the further growth of edge-enriched MoS₂ flakes. Thus, the coalescence takes place in different regions with the time. Therefore, instead of condensing on the edge-enriched MoS₂ flakes, MoS₂ condensed on the different regions, and the height of the edge-enriched MoS₂ flakes is small in comparison to that of MoS₂-100. Beyond 150 sccm of gas flow rate, the incoming S and Mo atoms have a higher probability to adsorb further, and this continues on the edges of MoS₂ flakes in comparison to the inert plane of vertically aligned MoS₂ flakes, which leads to larger size of MoS₂ flakes with lower density in comparison to MoS₂-150 sample. Therefore, the effective density of the edge-enriched MoS₂ in MoS₂-175 is less in comparison to MoS₂-150 sample. Figure 7d shows the side view of the edge-enriched MoS₂ flakes. The height of mostly edge-exposed flakes varies from 500 to 600 nm in all areas of the

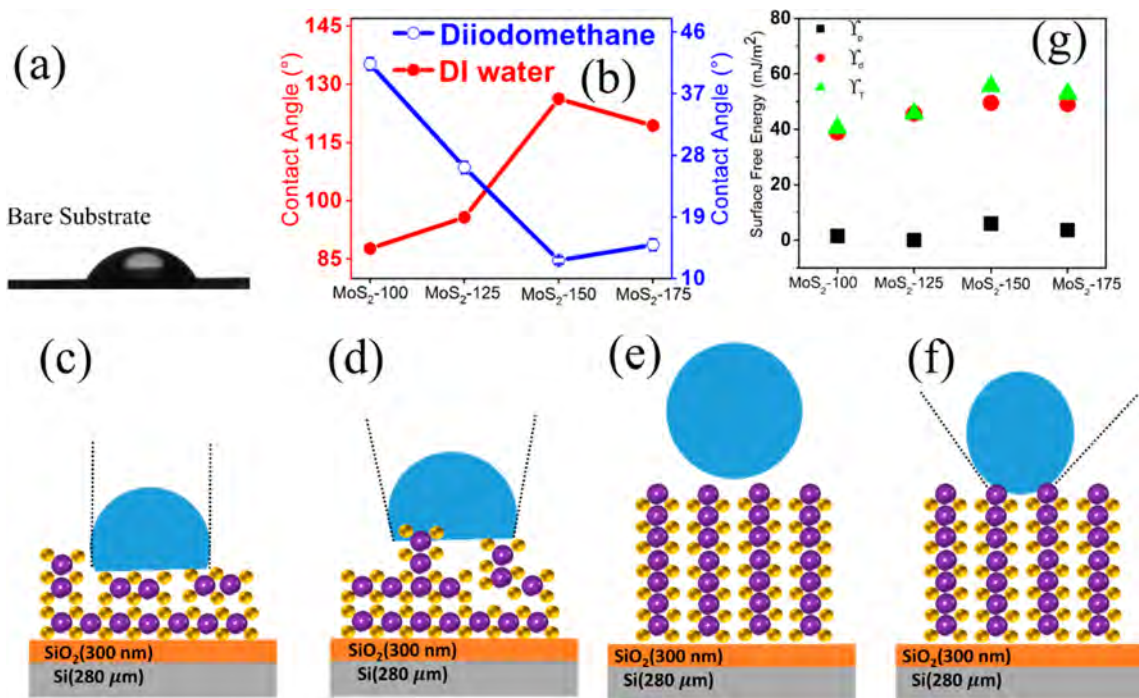


Figure 9. Wettability measurements and surface free energy study of different MoS₂ samples. Contact angle measured on (a) bare SiO₂/Si substrate with DI water. (b) Contact angle variation with DI water and diiodomethane on MoS₂ flakes synthesized at different gas flow rates. Wetting phenomenon of DI water with MoS₂ sample (c) with majority of in-plane MoS₂ (MoS₂-100) and (d) with in-plane MoS₂ and few layers of edge-enriched MoS₂ flakes (MoS₂-125). (e, f) Wenzel state to Cassie–Baxter state transition after the few seconds of droplet stabilization for the highly dense edge-enriched MoS₂ flakes (MoS₂-150 and MoS₂-175). (g) The variation of the total surface free energy with polar liquid and diiodomethane of MoS₂ flakes. It shows that the total surface free energy increases in controlled manner when the density of the edge-enriched MoS₂ flakes increases.

substrate. The Figure 7d and Figure 8a FE-SEM images clearly showed that the MoS₂ flakes growing on the in-plane MoS₂ are preferably vertically aligned to the substrate.

Finally, the contact angle measurements were performed on the different MoS₂ samples to understand their surface wettability and surface energies. Surface wettability is an important property of a 2D material system to understand the coating behavior, hydrogen evolution reactions, and cell proliferation.^{53–57} However, surface topology, crystallinity, and chemical composition of MoS₂ films strongly affect these properties.^{58–60} Previous reports observed hydrophobic nature of *in-plane* and edge-enriched MoS₂ flakes with the contact angle ranging from 87° to 98°.^{31,61–63} Gaur et al. showed that the variation in contact angle was due to growth temperature and orientation of the MoS₂ film from 23° to 98°. However, prepared MoS₂ sample was atomically smooth, so the effect of the roughness is considered negligible.^{60,64} Ganesh et al. observed super-hydrophobic nature of MoS₂ nanoflowers grown on graphite paper with a contact angle of 160°.²⁸ However, the high contact angle was attributed due to the high surface roughness of the MoS₂ nanoflower.

In this report, wettability behavior was studied by using two different liquids, namely, deionized water (DI) water (a polar liquid) and diiodomethane (a dispersive liquid). The behavior of the contact angle with a bare substrate for DI water and MoS₂ samples for two liquids is shown in Figure 9a,b.

The contact angle study for the synthesized samples with DI water shows an increase in the contact angle with the increase in the density of edge-enriched flakes, while contact angle decreased with diiodomethane for all the samples as the density of edge-enriched flakes increased. In case of the *in-plane*

dominated MoS₂ sample (MoS₂-100 and MoS₂-125), the contact angle for DI water was observed around 87.6° and 95.7°. Samples grown at 150 and 175 sccm show the increase in the hydrophobicity with an increase in the contact angle to 126.2° and 119.3°, respectively. The small decrease in the contact angle for the sample MoS₂-175 also revealed that the density of the flakes in MoS₂-175 sample is less in comparison to MoS₂-150 sample.

However, with diiodomethane, we obtained exactly opposite nature of wettability behavior for MoS₂ flakes. The higher value of contact angle, 41.3° and 26.2°, was observed for the sample grown at 100 and 125 sccm, while diiodomethane showed hydrophilic nature for the sample grown at 150 and 175 sccm with the contact angle of 12.6° and 14.9°, respectively. Thus, clearly DI water and diiodomethane have exactly opposite trend for the contact angle on variable-density MoS₂ flakes, and this can be attributed to the polar and dispersive nature of the liquids used. All the samples have high density of edges for a large droplet connecting region. The wetting behavior of the DI water droplets for the sample synthesized from 100 to 175 sccm is shown in Figure 9c–f. For the MoS₂ flakes at 150 and 175 sccm, density of the edge-enriched flakes is very high, and thus the contact angle increases for these samples, and droplets follow the transitions from the Cassie–Baxter state to the Wenzel state: decrease in contact angle with time and saturation after few seconds, as shown in Figure 9e,f. Stabilization of the droplets was studied for 10 min, and no change in the contact angle value is observed. The contact angle values for DI water and diiodomethane are affected with the variation of the density of edge-enriched MoS₂ flakes within the sample. To avoid any discrepancy that arises due to variation of

the edge-enriched MoS₂ flakes over the large area, the contact angle with both the liquids was performed at multiple locations on 1 × 2 cm² substrate, and an average value of contact angle is reported. The different values of the contact angle at multiple locations is tabulated in Tables S1 and S2 of the [Supporting Information](#).

Here we proposed the controlled increase in hydrophobic nature with DI water and the increase in hydrophilic nature with diiodomethane are due to change in the orientation of MoS₂ flakes from in-plane to out-of-plane edge-enriched MoS₂ flakes. Wettability analysis measures the attraction between the liquid and solid surface, which depends mainly on adhesive and cohesive forces. The adhesive force is an attractive force observed between the solid surface and the liquid surface. Cohesive force is observed between the molecules of the liquid droplet. The dramatic behavior of MoS₂ flakes with DI water and diiodomethane can be attributed to the nature of the liquids used in the experiment. DI water is a polar solvent with the surface free energy of 72 mJ/m², and diiodomethane is a dispersive liquid with the surface free energy of the order 50.8 mJ/m² at room temperature. Polar components of surface free energy arise due to Coulombic interactions between the permanent dipoles of atoms/molecules and the induced dipoles of atoms/molecules present at the surface, while the interactions due to fluctuations of the charge distribution in the atoms/molecules give rise to the dispersive interactions.⁶⁵

In the case of the DI water, the small increase in the contact angle value for the MoS₂-100 and MoS₂-125 is similar to previous reports for in-plane MoS₂ flakes.^{31,60,62–64} The variation of the contact angle for the DI water in all four samples may be due to the surface roughness and the increased density of the edge-enriched MoS₂ flakes.^{28,58,60–62} To understand more clearly, we studied the surface roughness for all four samples. To avoid any discrepancy, we measured the surface roughness at the multiple locations. The surface roughness is observed to be 87.6, 93.3, 60.4, and 55.7 nm for MoS₂-100, MoS₂-125, MoS₂-150, and MoS₂-175 samples, respectively. The data are shown in Figure S3 of the [Supporting Information](#). It has been found that the surface roughness is higher for the samples of MoS₂-100 and MoS₂-125 in comparison to that of MoS₂-150 and MoS₂-175. However, the contact angle is higher for the samples MoS₂-150 and MoS₂-175. Thus, the surface roughness study revealed that the density of the edge-enriched MoS₂ flakes is the dominant factor to determine the contact angle value for the DI water.

The edges have the reactive sites in the form of the S vacancy, dangling bonds and the active sites.^{13,28,66} DI water as a polar liquid affected these active sites, and thus the contact angle with DI water increased with these edges of the MoS₂ flakes. The small increase in the contact angle value for the samples MoS₂-100 and MoS₂-125 may be attributed to the increased density of the MoS₂ edges.²⁸

In case of the diiodomethane, due to dispersive nature of the diiodomethane, contact angle with the diiodomethane is affected by the fluctuations of the charge distribution in the atoms/molecules at the surface. It has been reported that the edges of the MoS₂ behave as the metallic 1D nanowires.^{31,67,68} The defects are present at the edges in the form of the S vacancies, which are produced during the growth.⁶⁹ The S vacancies are easy to produce in comparison to the Mo vacancy, since the energy required to remove the S and Mo atoms is 6.1 and 13.9 eV.⁷⁰ As the S is removed from them, the edges contain mostly the Mo atom, making them Mo-rich. As a

transition metal, it has metallic nature, and it increases the conductivity of the highly uniform edge-enriched MoS₂ flakes.⁶⁷ Thus, increase in the density increases the metallic-like nature of the edges and the interaction of the diiodomethane. This may result in higher electron density at the edges of the MoS₂. MoS₂ samples grown at lower gas flow rates, 100 and 125 sccm, contain in-plane and isolated edge-enriched MoS₂ flakes as shown in [Figure 2](#); hence, they have the less interaction.⁶⁷ The interaction of diiodomethane liquid increase more and becomes density-dependent as the density of edge-enriched MoS₂ flakes increases because of increased fluctuations in electron charge density. Because of high availability of the edges in the MoS₂-150, the contact angle is lower in comparison for all the samples.

The surface free energy of variable edge-enriched MoS₂ flakes was then measured using Fowkes methods. The surface free energy is the sum of polar and dispersive components, and surface free energy can be determined by using polar (DI water) and dispersive liquid (diiodomethane).⁶⁵ Wettability of the surface depends on the surface free energy of liquids and interaction with the solid surface.

The surface free energy of the liquid, solid–liquid, and solid is balanced by the Young's equation

$$\gamma_s = \gamma_{sl} + \gamma_l \cos \theta \quad (3)$$

where γ_s , γ_{sl} , and γ_l are the surface free energy of solid, solid–liquid, and liquids used.

In Fowkes method, surface free energy is determined by the polar and dispersive liquids. One liquid should have zero polar component like diiodomethane, $\gamma_l = \gamma_l^d = 50.8 \text{ mJ/m}^2$, while the other liquid should have the sum of dominant polar and dispersive components like DI water, $\gamma_l^p = 51 \text{ mJ/m}^2$, $\gamma_l^d = 21.8 \text{ mJ/m}^2$, where γ_l^p and γ_l^d are the polar and dispersive component of liquid. Sum of the polar and dispersive components of interfacial energy of the solid gives the total surface energy of the solid. DI water and diiodomethane are used as the polar and dispersive liquids. Fowkes method considers the solid–liquid interactions (two-phase interactions). For system having the only dispersive components, the dispersive surface free energy component is evaluated by

$$\gamma_{sl} = \gamma_s + \gamma_l - 2(\gamma_s^d \gamma_l^d)^{0.5} \quad (4)$$

Combining eqs 3 and (4) and considering that liquid has no polar component then $\gamma_l = \gamma_l^d$ results in modified equation; the dispersive components of surface free energy can be calculated by

$$\gamma_l = \gamma_s^d = 0.25\gamma_l^d(1 + \cos \theta_d)^2 \quad (5)$$

For the liquid having both components like DI water, $\gamma_l = \gamma_p + \gamma_d$. The eq 4 has one additional polar terms

$$\gamma_{sl} = \gamma_s + \gamma_l - 2(\gamma_s^d \gamma_l^d)^{0.5} - 2(\gamma_s^p \gamma_l^p)^{0.5} \quad (6)$$

With eq 3 and eq 6, surface free energy of the polar liquid is given by

$$\gamma_s^p = \frac{[0.5\gamma_l(1 + \cos \theta_p) - ((\gamma_s^d \gamma_l^d)^{0.5})]^2}{\gamma_l^p} \quad (7)$$

where γ_l^d and γ_l^p are the dispersive and polar components of liquid, and γ_s^d and γ_s^p are the dispersive and polar components of solid.

Table 2. Measured Contact Angles and Surface Free Energy of Polar and Dispersive Liquids on the MoS₂ Surface Synthesized Using Different Conditions

sample	contact angle for different liquids		surface free energy by Fowkes method, mJ/m ²		
	DI water	diiodomethane	γ_p (polar components)	γ_d (dispersive components)	γ_T (sum of components)
	CA, ^a deg	CA, ^a deg			
MoS ₂ -100	87.6	41.3	1.5	38.9	40.4
MoS ₂ -125	95.7	26.2	0.03	45.7	45.7
MoS ₂ -150	126.2	12.6	6.0	49.5	55.6
MoS ₂ -175	119.3	14.9	3.7	49.1	52.8

^aCA = contact angle, γ_p = polar component of surface free energy, γ_d = dispersive component of surface free energy, γ_T = surface free energy.

The calculated values of polar and dispersive components of surface free energy are shown in Table 2. Variation of polar components and dispersive components is shown in Figure 9g. Total surface free energy is also plotted, which shows the controlled variation with the density of edge-enriched MoS₂ flakes. In our case, with increasing contact angle surface free energy components for both polar and dispersive liquids decreased. However, the total surface free energy (sum of the dispersive and polar surface free energy components) increased as the density of flakes increased and has the highest value for MoS₂-150 sample. The samples MoS₂-100 and MoS₂-125, which mostly contain in-plane MoS₂ flakes, show the total surface free energy on the order of 40.4 and 45.7 mJ/m² and are similar to those reported in the literature for similar layer in-plane MoS₂ flakes, 46.5 mJ/m², while the edge-enriched flakes have the total surface free energy on the order of the 55.6 and 52.8 mJ/m².³¹ However, no studies for the surface free energy of edge-enriched MoS₂ flakes have been done, to the best of our knowledge. In the cases of MoS₂-150 and MoS₂-175, it is observed from the SEM images shown in Figures 2 and 3 that the density of edge-enriched MoS₂ flakes is higher in MoS₂-150 in comparison to MoS₂-175. The surface free energy is the sum of the surface energy of the dispersive liquids and the polar liquids in the Fowkes method. Because of very high density of edge-enriched MoS₂ flakes in the MoS₂-150 sample, the edge-enriched MoS₂ flakes have higher effect on the surface free energy components that arises due to the diiodomethane/DI sample, as the edges have the more reactive sites in comparison to the in-plane MoS₂ flakes, and water is a polar liquid. The reactivity of the water molecules increases with the increase in the active sites; hence, the DI water contact angle increased. With the diiodomethane, increase in the edges correspondingly increase the electron concentration, which also increase the interaction of the dispersive liquid. Thus, in MoS₂-150 sample, the contact angle with DI water/diiodomethane is highest/lowest. So, the total surface free energy is also slightly higher with MoS₂-150.

CONCLUSION

In summary, controlled and tunable growth of the interconnected edge-enriched 3D network of MoS₂ flakes is reported by using modified tube-in-tube APCVD method. The MoS₂ flakes were grown at different gas flow rates to control their density from stand-alone MoS₂ flakes to well-connected 3D MoS₂ flakes network. The detailed morphology, structural, and optical analyses of MoS₂ flakes revealed that the growth of vertical MoS₂ flake starts from in-plane MoS₂, and by increases in gas flow rate the density of edge-enriched MoS₂ flakes increases. The contact angle values for DI water and diiodomethane are measured. Contact angle values for both the

liquids are strongly depended upon the density of the edge-enriched MoS₂ flakes. The surface energy of MoS₂ edge structures with different density was evaluated by sessile contact angle measurement with polar (water) and dispersive (diiodomethane) liquids. The total surface free energy was observed to increase with the density of edge-enriched MoS₂ flakes. The proposed growth mechanism for edge-enriched MoS₂ flakes and their surface energy studies may be useful to design TMDC materials with desirable properties for different applications.

ASSOCIATED CONTENT

Supporting Information

The Supporting Information is available free of charge on the ACS Publications website at DOI: 10.1021/acsanm.8b00467.

Optical and FE-SEM images of the highly uniform MoS₂ samples with different gas flow rates on SiO₂/Si substrate, optical and FE-SEM images of the highly uniform MoS₂ samples on the different substrates, atomic force microscopy surface roughness measurements, XRD of MoS₂-100, MoS₂-125, MoS₂-150, and MoS₂-175 samples, cross-sectional TEM data obtained from the MoS₂-100 and MoS₂-175 samples, synthesis of MoS₂ flakes at 800° for 10 min at 150 sccm, confirmation of growth mechanism using AFM study: contact angle measurements at different locations for DI water and diiodomethane (PDF)

AUTHOR INFORMATION

Corresponding Author

*E-mail: mkumar@iitpr.ac.in.

ORCID

Abhay V. Agrawal: 0000-0002-2940-6050

Alex Zakhidov: 0000-0001-6980-2659

Zhuan Zhu: 0000-0003-4377-9053

FC Robles Hernandez: 0000-0001-5587-0802

Jiming Bao: 0000-0002-6819-0117

Mukesh Kumar: 0000-0001-6389-2040

Notes

The authors declare no competing financial interest.

ACKNOWLEDGMENTS

We sincerely acknowledge the grant from Board of Research in Nuclear Sciences, Department of Atomic Energy, under Young Scientist Research Awards (Grant No. 34/20/09/2015/BRNS/).

REFERENCES

(1) Balendhran, S.; Walia, S.; Nili, H.; Ou, J. Z.; Zhuiykov, S.; Kaner, R. B.; Sriram, S.; Bhaskaran, M.; Kalantar-zadeh, K. Two-Dimensional

Molybdenum Trioxide and Dichalcogenides. *Adv. Funct. Mater.* **2013**, *23*, 3952–3970.

(2) Wang, Q. H.; Kalantar-Zadeh, K.; Kis, A.; Coleman, J. N.; Strano, M. S. Electronics and Optoelectronics of Two-Dimensional Transition Metal Dichalcogenides. *Nat. Nanotechnol.* **2012**, *7*, 699–712.

(3) Splendiani, A.; Sun, L.; Zhang, Y.; Li, T.; Kim, J.; Chim, C.-Y.; Galli, G.; Wang, F. Emerging Photoluminescence in Monolayer MoS₂. *Nano Lett.* **2010**, *10*, 1271–1275.

(4) Mak, K. F.; Lee, C.; Hone, J.; Shan, J.; Heinz, T. F. Atomically Thin MoS₂: A New Direct-Gap Semiconductor. *Phys. Rev. Lett.* **2010**, *105*, 136805.

(5) Shanmugam, M.; Durcan, C. A.; Yu, B. Layered Semiconductor Molybdenum Disulfide Nanomembrane Based Schottky-Barrier Solar Cells. *Nanoscale* **2012**, *4*, 7399–7405.

(6) Liu, C.; Kong, D.; Hsu, P.-C.; Yuan, H.; Lee, H.-W.; Liu, Y.; Wang, H.; Wang, S.; Yan, K.; Lin, D.; Maraccini, P. A.; Parker, K. M.; Boehm, A. B.; Cui, Y. Rapid Water Disinfection Using Vertically Aligned MoS₂ Nanofilms and Visible Light. *Nat. Nanotechnol.* **2016**, *11*, 1098–1104.

(7) Radisavljevic, B.; Radenovic, A.; Brivio, J.; Giacometti, V.; Kis, A. Single-Layer MoS₂ Transistors. *Nat. Nanotechnol.* **2011**, *6*, 147–150.

(8) Kibsgaard, J.; Chen, Z.; Reinecke, B. N.; Jaramillo, T. F. Engineering the Surface Structure of MoS₂ to Preferentially Expose Active Edge Sites For Electrocatalysis. *Nat. Mater.* **2012**, *11*, 963–969.

(9) Jaramillo, T. F.; Jorgensen, K. P.; Bonde, J.; Nielsen, J. H.; Horch, S.; Chorkendorff, I. Identification of Active Edge Sites for Electrochemical H₂ Evolution from MoS₂ Nanocatalysts. *Science* **2007**, *317*, 100–102.

(10) Raja, R.; Sudhagar, P.; Devadoss, A.; Terashima, C.; Shrestha, L. K.; Nakata, K.; Jayavel, R.; Ariga, K.; Fujishima, A. Pt-Free Solar Driven Photoelectrochemical Hydrogen Fuel Generation Using 1T MoS₂ Co-Catalyst Assembled Cds Qds/TiO₂ Photoelectrode. *Chem. Commun.* **2015**, *51*, 522–525.

(11) Ye, G.; Gong, Y.; Lin, J.; Li, B.; He, Y.; Pantelides, S. T.; Zhou, W.; Vajtai, R.; Ajayan, P. M. Defects Engineered Monolayer MoS₂ for Improved Hydrogen Evolution Reaction. *Nano Lett.* **2016**, *16*, 1097–1103.

(12) Deokar, G.; Rajput, N.; Vancsó, P.; Ravoux, F.; Jouiad, M.; Vignaud, D.; Cecchet, F.; Colomer, J.-F. Large Area Growth of Vertically Aligned Luminescent MoS₂ Nanosheets. *Nanoscale* **2017**, *9*, 277–287.

(13) Hu, J.; Huang, B.; Zhang, C.; Wang, Z.; An, Y.; Zhou, D.; Lin, H.; Leung, M. K. H.; Yang, S. Engineering Stepped Edge Surface Structures of MoS₂ Sheet Stacks to Accelerate the Hydrogen Evolution Reaction. *Energy Environ. Sci.* **2017**, *10*, 593–603.

(14) Zhou, Y.; Liu, Y.; Zhao, W.; Xie, F.; Xu, R.; Li, B.; Zhou, X.; Shen, H. Growth of Vertically Aligned MoS₂ Nanosheets on a Ti Substrate Through a Self-Supported Bonding Interface for High-Performance Lithium-Ion Batteries: A General Approach. *J. Mater. Chem. A* **2016**, *4*, 5932–5941.

(15) Ling, L.; Wang, C.; Zhang, K.; Li, T.; Tang, L.; Li, C.; Wang, L.; Xu, Y.; Song, Q.; Yao, Y. Controlled Growth of MoS₂ Nanopetals and Their Hydrogen Evolution Performance. *RSC Adv.* **2016**, *6*, 18483–18489.

(16) Wang, S.; Rong, Y.; Fan, Y.; Pacios, M.; Bhaskaran, H.; He, K.; Warner, J. H. Shape Evolution of Monolayer MoS₂ Crystals Grown By Chemical Vapor Deposition. *Chem. Mater.* **2014**, *26*, 6371–6379.

(17) Kang, K.; Xie, S.; Huang, L.; Han, Y.; Huang, P. Y.; Mak, K. F.; Kim, C. J.; Muller, D.; Park, J. High-Mobility Three-Atom-Thick Semiconducting Films with Wafer-Scale Homogeneity. *Nature* **2015**, *520*, 656–660.

(18) Tan, L. K.; Liu, B.; Teng, J. H.; Guo, S.; Low, H. Y.; Loh, K. P. Atomic Layer Deposition of a MoS₂ Film. *Nanoscale* **2014**, *6*, 10584–10588.

(19) Muralikrishna, S.; Manjunath, K.; Samrat, D.; Reddy, V.; Ramakrishna, T.; Nagaraju, D. H. Hydrothermal Synthesis of 2D MoS₂ Nanosheets for Electrocatalytic Hydrogen Evolution Reaction. *RSC Adv.* **2015**, *5*, 89389–89396.

(20) Wang, F. Z.; Zheng, M. J.; Zhang, B.; Zhu, C. Q.; Li, Q.; Ma, L.; Shen, W. Z. Ammonia Intercalated Flower-Like MoS₂ Nanosheet Film as Electrocatalyst for High Efficient and Stable Hydrogen Evolution. *Sci. Rep.* **2016**, *6*, 31092.

(21) Shi, Y.; Li, H.; Wong, J. I.; Zhang, X.; Wang, Y.; Song, H.; Yang, H. Y. MoS₂ Surface Structure Tailoring via Carbonaceous Promoter. *Sci. Rep.* **2015**, *5*, 10378.

(22) Yu, Y.; Li, C.; Su, L.; Zhang, Y.; Cao, L. Controlled Scalable Synthesis of Uniform, High-Quality Monolayer and few-Layer MoS₂ Films. *Sci. Rep.* **2013**, *3*, 1866.

(23) Li, S.; Wang, S.; Salamone, M. M.; Robertson, A. W.; Nayak, S.; Kim, H.; Tsang, S. C. E.; Pasta, M.; Warner, J. H. Edge-Enriched 2D MoS₂ Thin Films Grown by Chemical Vapor Deposition for Enhanced Catalytic Performance. *ACS Catal.* **2017**, *7*, 877–886.

(24) Gong, Y.; Lin, J.; Wang, X.; Shi, G.; Lei, S.; Lin, Z.; Zou, X.; Ye, G.; Vajtai, R.; Yakobson, B. I.; Terrones, H.; Terrones, M.; Tay, B. K.; Lou, J.; Pantelides, S. T.; Liu, Z.; Zhou, W.; Ajayan, P. M. Vertical and In-Plane Heterostructures From WS₂/MoS₂ Monolayers. *Nat. Mater.* **2014**, *13*, 1135.

(25) Li, H.; Wu, H.; Yuan, S.; Qian, H. Synthesis And Characterization of Vertically Standing MoS₂ Nanosheets. *Sci. Rep.* **2016**, *6*, 21171.

(26) Kong, D.; Wang, H.; Cha, J. J.; Pasta, M.; Koski, K. J.; Yao, J.; Cui, Y. Synthesis of MoS₂ and MoSe₂ Films with Vertically Aligned Layers. *Nano Lett.* **2013**, *13*, 1341–1347.

(27) Zhang, X.; Zhang, S.; Chen, B.; Wang, H.; Wu, K.; Chen, Y.; Fan, J.; Qi, S.; Cui, X.; Zhang, L.; Wang, J. Direct Synthesis of Large-Scale Hierarchical MoS₂ Films Nanostructured with Orthogonally Oriented Vertically and Horizontally Aligned Layers. *Nanoscale* **2016**, *8*, 431–439.

(28) Bhimanapati, G. R.; Hankins, T.; Lei, Y.; Vila, R. A.; Fuller, I.; Terrones, M.; Robinson, J. A. Growth and Tunable Surface Wettability of Vertical MoS₂ Layers for Improved Hydrogen Evolution Reactions. *ACS Appl. Mater. Interfaces* **2016**, *8*, 22190–22195.

(29) Van der Zande, A. M.; Huang, P. Y.; Chenet, D. A.; Berkelbach, T. C.; You, Y.; Lee, G.-H.; Heinz, T. F.; Reichman, D. R.; Muller, D. A.; Hone, J. C. Grains and Grain Boundaries in Highly Crystalline Monolayer Molybdenum Disulfide. *Nat. Mater.* **2013**, *12*, 554–561.

(30) Li, Y.; Dong, N.; Zhang, S.; Zhang, X.; Feng, Y.; Wang, K.; Zhang, L.; Wang, J. Giant Two-Photon Absorption in Monolayer MoS₂. *Laser & Photonics Reviews* **2015**, *9*, 427–434.

(31) Gaur, A. P.; Sahoo, S.; Ahmadi, M.; Dash, S. P.; Guinel, M. J.; Katiyar, R. S. Surface Energy Engineering for Tunable Wettability Through Controlled Synthesis of MoS₂. *Nano Lett.* **2014**, *14*, 4314–4321.

(32) Wang, C.; Chen, W.; Han, C.; Wang, G.; Tang, B.; Tang, C.; Wang, Y.; Zou, W.; Chen, W.; Zhang, X.-A.; Qin, S.; Chang, S.; Wang, L. Growth of Millimeter-Size Single Crystal Graphene on Cu Foils by Circumfluence Chemical Vapor Deposition. *Sci. Rep.* **2015**, *4*, 4537.

(33) Deng, J.; Yuan, W.; Ren, P.; Wang, Y.; Deng, D.; Zhang, Z.; Bao, X. High-Performance Hydrogen Evolution Electrocatalysis by Layer-Controlled MoS₂ Nanosheets. *RSC Adv.* **2014**, *4*, 34733–34738.

(34) Verble, J. L.; Wieting, T. J. Lattice Mode Degeneracy in MoS₂ and Other Layer Compounds. *Phys. Rev. Lett.* **1970**, *25*, 362–365.

(35) Wieting, T. J.; Verble, J. L. Infrared and Raman Studies of Long Wavelength Optical Phonons in Hexagonal MoS₂. *Phys. Rev. B* **1971**, *3*, 4286–4292.

(36) Phuc, N. H. H.; Okuno, T.; Hakiri, N.; Kawamura, G.; Matsuda, A.; Muto, H. Synthesis of High-Edge Exposure MoS₂ Nano Flakes. *J. Nanopart. Res.* **2014**, *16*, 2199.

(37) Yu, H.; Yu, X.; Chen, Y.; Zhang, S.; Gao, P.; Li, C. A Strategy To Synergistically Increase the Number of Active Edge Sites and the Conductivity of MoS₂ Nanosheets for Hydrogen Evolution. *Nanoscale* **2015**, *7*, 8731–8738.

(38) Ganatra, R.; Zhang, Q. Few-Layer MoS₂: A Promising Layered Semiconductor. *ACS Nano* **2014**, *8*, 4074–4099.

(39) Molina-Sanchez, A.; Wirtz, L. Phonons in Single-Layer and Few-Layer MoS₂ and WS₂. *Phys. Rev. B: Condens. Matter Mater. Phys.* **2011**, *84*, 155413.

- (40) Kumar, P.; Singh, M.; Sharma, R. K.; Reddy, G. B. Reaction Mechanism of Core–Shell MoO₂/MoS₂ Nanoflakes via Plasma-Assisted Sulfurization of MoO₃. *Mater. Res. Express* **2016**, *3*, 055021.
- (41) Lee, C.; Yan, H.; Brus, L. E.; Heinz, T. F.; Hone, J.; Ryu, S. Anomalous Lattice Vibrations of Single and Few Layer MoS₂. *ACS Nano* **2010**, *4*, 2695–2700.
- (42) Li, B.; Yang, S.; Huo, N.; Li, Y.; Yang, J.; Li, R.; Fan, C.; Lu, F. Growth of Large Area Few-Layer or Monolayer MoS₂ from Controllable MoO₃ Nanowire Nuclei. *RSC Adv.* **2014**, *4*, 26407–26412.
- (43) Eda, G.; Yamaguchi, H.; Voiry, D.; Fujita, T.; Chen, M.; Chhowalla, M. Photoluminescence from Chemically Exfoliated MoS₂. *Nano Lett.* **2011**, *11*, 5111–5116.
- (44) Coehoorn, R.; Haas, C.; de Groot, R. A. Electronic Structure of MoSe₂, MoS₂, and WSe₂. II. The Nature of The Optical Band Gaps. *Phys. Rev. B: Condens. Matter Mater. Phys.* **1987**, *35*, 6203–6206.
- (45) Nan, H.; Wang, Z.; Wang, W.; Liang, Z.; Lu, Y.; Chen, Q.; He, D.; Tan, P.; Miao, F.; Wang, X.; et al. Strong Photoluminescence Enhancement of MoS₂ Through Defect Engineering and Oxygen Bonding. *ACS Nano* **2014**, *8*, 5738–5745.
- (46) Li, T.; Galli, G. Electronic Properties of MoS₂ Nanoparticles. *J. Phys. Chem. C* **2007**, *111*, 16192–16196.
- (47) Ghosh, P. N. Davydov Splitting And Multipole Interactions. *Solid State Commun.* **1976**, *19*, 639–642.
- (48) Ghosh, P. N.; Maiti, C. R. Interlayer Force And Davydov Splitting in 2H - MoS₂. *Phys. Rev. B: Condens. Matter Mater. Phys.* **1983**, *28*, 2237–2239.
- (49) Wieting, T. J.; Verble, J. L. Interlayer Bonding and The Lattice Vibrations of β -GaSe. *Phys. Rev. B* **1972**, *5*, 1473–1479.
- (50) Zhang, S.; Yu, X.; Yu, H.; Chen, Y.; Gao, P.; Li, C.; Zhu, C. Growth of Ultrathin MoS₂ Nanosheets with Expanded Spacing of (002) Plane on Carbon Nanotubes for High-Performance Sodium-Ion Battery Anodes. *ACS Appl. Mater. Interfaces* **2014**, *6*, 21880–21885.
- (51) Yu, H.; Zhu, C.; Zhang, K.; Chen, Y.; Li, C.; Gao, P.; Yang, P.; Ouyang, Q. Three-Dimensional Hierarchical MoS₂ Nanoflake Array/Carbon Cloth as High-Performance Flexible Lithium-Ion Battery Anodes. *J. Mater. Chem. A* **2014**, *2*, 4551–4557.
- (52) Ohring, M. Film Formation and Structure. In *The Materials Science of Thin Films*; Academic Press: San Diego, CA, 1992; pp 195–247.
- (53) Ma, C.-B.; Qi, X.; Chen, B.; Bao, S.; Yin, Z.; Wu, X.-J.; Luo, Z.; Wei, J.; Zhang, H.-L.; Zhang, H. MoS₂ Nanoflower-Decorated Reduced Graphene Oxide Paper for High-Performance Hydrogen Evolution Reaction. *Nanoscale* **2014**, *6*, 5624–5629.
- (54) Lukowski, M. A.; Daniel, A. S.; Meng, F.; Forticaux, A.; Li, L.; Jin, S. Enhanced Hydrogen Evolution Catalysis from Chemically Exfoliated Metallic MoS₂ Nanosheets. *J. Am. Chem. Soc.* **2013**, *135*, 10274–10277.
- (55) Chen, S.; Brown, L.; Levendorf, M.; Cai, W.; Ju, S.-Y.; Edgeworth, J.; Li, X.; Magnuson, C. W.; Velamakanni, A.; Piner, R. D.; Kang, J.; Park, J.; Ruoff, R. S. Oxidation Resistance of Graphene-Coated Cu and Cu/Ni Alloy. *ACS Nano* **2011**, *5*, 1321–1327.
- (56) Wang, Y.; Li, Z.; Wang, J.; Li, J.; Lin, Y. Graphene and Graphene Oxide: Biofunctionalization And Applications In Biotechnology. *Trends Biotechnol.* **2011**, *29*, 205–212.
- (57) Chen, H.; Müller, M. B.; Gilmore, K. J.; Wallace, G. G.; Li, D. Mechanically Strong, Electrically Conductive, and Biocompatible Graphene Paper. *Adv. Mater.* **2008**, *20*, 3557–3561.
- (58) Drelich, J.; Miller, J. D.; Kumar, A.; Whitesides, G. M. Wetting Characteristics of Liquid Drops at Heterogeneous Surfaces. *Colloids Surf., A* **1994**, *93*, 1–13.
- (59) Lopez, G.; Biebuyck, H.; Frisbie, C.; Whitesides, G. Imaging of Features on Surfaces by Condensation Figures. *Science* **1993**, *260*, 647–649.
- (60) Latthe, S.; Terashima, C.; Nakata, K.; Fujishima, A. Superhydrophobic Surfaces Developed by Mimicking Hierarchical Surface Morphology of Lotus Leaf. *Molecules* **2014**, *19*, 4256–4283.
- (61) Chow, P. K.; Singh, E.; Viana, B. C.; Gao, J.; Luo, J.; Li, J.; Lin, Z.; Elías, A. L.; Shi, Y.; Wang, Z.; Terrones, M.; Koratkar, N. Wetting of Mono and Few-Layered WS₂ and MoS₂ Films Supported on Si/SiO₂ Substrates. *ACS Nano* **2015**, *9*, 3023–3031.
- (62) Kelebek, S. Critical Surface Tension of Wetting and of Floatability of Molybdenite and Sulfur. *J. Colloid Interface Sci.* **1988**, *124*, 504–514.
- (63) Zhang, S.; Zeng, X.; Tang, Z.; Tan, M. J. Exploring the Antisticking Properties of Solid Lubricant Thin Films In Transfer Molding. *Int. J. Mod. Phys. B* **2002**, *16*, 1080–1085.
- (64) Patankar, N. A. On the Modeling of Hydrophobic Contact Angles on Rough Surfaces. *Langmuir* **2003**, *19*, 1249–1253.
- (65) Fowkes, F. M. Attractive Forces At Interfaces. *Ind. Eng. Chem.* **1964**, *56*, 40–52.
- (66) Jaramillo, T. F.; Jorgensen, K. P.; Bonde, J.; Nielsen, J. H.; Horch, S.; Chorkendorff, I. Identification of active edge sites for electrochemical H₂ evolution from MoS₂ nanocatalysts. *Science* **2007**, *317* (5834), 100–2.
- (67) Bollinger, M. V.; Lauritsen, J. V.; Jacobsen, K. W.; Nørskov, J. K.; Helveg, S.; Besenbacher, F. One-Dimensional Metallic Edge States in MoS₂. *Phys. Rev. Lett.* **2001**, *87*, 196803.
- (68) Agrawal, A. V.; Kumar, R.; Venkatesan, S.; Zakhidov, A.; Zhu, Z.; Bao, J.; Kumar, M.; Kumar, M. Fast Detection and Low Power Hydrogen Sensor Using Edge-Oriented Vertically Aligned 3-D Network of MoS₂ Flakes at Room Temperature. *Appl. Phys. Lett.* **2017**, *111*, 093102.
- (69) Lv, R.; Robinson, J. A.; Schaak, R. E.; Sun, D.; Sun, Y.; Mallouk, T. E.; Terrones, M. Transition Metal Dichalcogenides and Beyond: Synthesis, Properties, and Applications of Single- and Few-Layer Nanosheets. *Acc. Chem. Res.* **2015**, *48*, 56–64.
- (70) Liu, X.; Xu, T.; Wu, X.; Zhang, Z.; Yu, J.; Qiu, H.; Hong, J.-H.; Jin, C.-H.; Li, J.-X.; Wang, X.-R.; Sun, L.-T.; Guo, W. Top–Down Fabrication of Sub-Nanometre Semiconducting Nanoribbons Derived From Molybdenum Disulfide Sheets. *Nat. Commun.* **2013**, *4*, 1776.